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Chemical-mechanical polishing, a process that is used in the semiconductor industry to isolate and connect individual transistors on a chip. The CMP process has been the fastest-growing semiconductor operation in the last decade, and its future growth is being fueled by the introduction of copper-based interconnects in advanced

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manufacturing, and
even more so as device
dimensions continue to

shrink. The technology has grown to encompass the removal and planarization of multiple metal and dielectric materials and layers both at the device and the metallization levels, using different tools and parameters, requiring improvements in the control of ...

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- Knovel

Therefore,
chemical—mechanical
planarization (CMP) is a
key process in the final
definition of the inlaid
copper wires on a
circuit. A second
advance in the back-
end processing of
copper is the changing
of the dielectric from
SiO₂ to a Low-k
material, which allows
a thicker layer of

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dielectric to be used.

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Taesung Kim. A
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was investigated to
improve non-uniformity
in a chemical
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planarization (CMP)
process. During the
CMP process, the
stress distribution on
the wafer...

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Chemical Mechanical Planarization Chemical mechanical polishing (CMP) is a powerful fabrication technique that uses chemical oxidation and mechanical abrasion to remove material and achieve very high levels of planarity.

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The effects of consumables on material removal and scratch propensity in Chemical Mechanical Planarization. Chapter 5 in Recent Advances in Abrasives Research (Bähre, Dirk, editor), Nova Science ...

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lower latency than
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was originally
developed to overcome
processing issues in
microelectronics
manufacturing, such as
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planarization is a
process of smoothing
surfaces with the
combination of
chemical and
mechanical forces. It
can be thought of as a
hybrid of chemical
etching and free
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